PLUS

	L#	Hits	Search T xt	DBs	Tim Stamp	Туре
1	L1	50	("4294404" "5778075" "5794147" "5870673" "6285881" "6792323" "4761641" "5826117" "5850577" "5305037" "5504935" "4509842" "5371566" "6144312" "4403285" "4425531" "4793980" "4805112" "4827410" "4835679" "4918379" "4971796" "5177524" "5267085" "5339126" "5392159" "5392502" "5442779" "5522028" "5568545" "5663954" "5692223" "5740070" "5844805" "5966550" "5986586" "6021514" "6034723" "6041515" "6209034" "6241456" "6247028" "6339670" "6407417" "6409198" "6457654" "4281775" "4246776" "4261132" "4335376").pn.	IUSPAT	2004/12/12 10:03	BRS

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Most Frequently Occurring Classifications of Patents Returned From A Search of 10749698 on November 26, 2004

Original Classifications

2 455/434

Cross-Reference Classifications

- 3 455/552.1
- 2 345/179
- 2 359/705
- 2 359/823
- 2 375/216
- 2 396/89 2 455/454
- 2 455/67.11

Combined Classifications

- 3 455/434
- 3 455/552.1
- 2 345/179
- 2 359/694
- 2 359/705
- 2 359/823
- 2 375/216
- 2 396/103
- 2 396/79
- 2 396/82
- 2 396/85
- 2 396/89
- 2 455/454
- 2 455/67.11 2 700/180

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	L#	Hits	Search Text	DBs	Tim Stamp	Туре
1	L1	67305	process ADJ control	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 10:21	BRS
2	L2	426	L1 SAME recipe	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 10:21	BRS
3	L3	116	L2 SAME (prior OR past OR feedback OR feed ADJ back OR histor\$ OR previous\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 10:25	BRS
4	L4	569	RBR OR "run-by -run"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 12:28	BRS
5	L5	1	L3 AND L4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 10:25	BRS
6	L6	73	L4 SAME (prior OR past OR feedback OR feed ADJ back OR histor\$ OR previous\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 10:26	BRS
7	L7	115	L3 NOT (L5 OR L6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 10:26	BRS
8	L8	12	("6249712").URPN.	USPAT	2004/12/12 11:35	BRS
9	L10	296	L4 NOT (L5 OR L6 OR L7 OR L8)	USPAT	2004/12/12 12:28	BRS
10	L11	10	("6587744").URPN.	USPAT	2004/12/12 11:53	BRS
11	L12	41	("5926690").URPN.	USPAT	2004/12/12 12:05	BRS
12	L13	0	("6625513").URPN.	USPAT	2004/12/12 12:08	BRS
13	L14	686	"run-by-run" OR "run-to-run"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/12/12 12:28	BRS
14	L15	424	L14 NOT (L5 OR L6 OR L7 OR L8 OR L10 OR L11 OR L12)	USPAT	2004/12/12 12:29	BRS
15	L16	160	L15 AND (L1 OR recipe)	USPAT	2004/12/12 12:29	BRS

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12/12/04, EAST Version: 2.0.1.4

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E	7	20040110310 A1	PUB	20040610	MULTIVARIATE RBR TOOL AGING DETECTOR	438/5	Sun, Cheng-I et al.	r	R C	: c	US 20040110310	ı c	
1	?	US 6249712 B1	USPAT	20010619	Adaptive control process and system	700/31	Boiquaye; William J. N-O.	r	nr	c	US 6249712	c	
r		US 6408220 B1	USPAT	20020618	Semiconductor processing techniques	700/121	Nulman; Jaim	7	r: r	· r	US 6408220	Г	
,	7	US 6798883 B1	USPAT	20040928	Controlled lubricated finishing	451/41	Molnar, Charles	-			US 6796883	n	
		US 6745086	USPAT	20040601	Method and apparatus for	700/28	J. Pasadyn;	i i		1	;		
Ľ	i	B1 US 6719615	USPAT	20040413	determining control actions incorporation defectivity effect Versatile wafer refining	451/41	Pasadyn; Alexander J. et al	.	I: 1.	# L .	US 6719615	1.:8	
r	-	B1		20030701	_		Molnar, Charles J.	ii		<u>İ.</u>	:	n	
F	7	B1			in microelectronic fabrication		Stoddard; Kevir D. et al.	r		ī	US 6587744	Г	
r		US 6773931 B2	USPAT	20040810	Dynamic targeting for a process control system	438/10	Pasadyn; Alexander J. et	P.	г. г	г	US 6773931	г	
ľ	-	US 6751518 B1	USPAT	20040815	Dynamic process state adjustment of a processing	700/121	Sonderman; Thomas J. et al	P.		ī	US 6751518	Г	
5	7	US 6701206 B1	USPAT	20040302	tool to reduce con-uniformity Method and system for controlling a process tool	700/121	Markle; Richard J. et al.	n I	ייי מונו	o co	US 6701206	r	
	-		USPAT	20040224	Method and apparatus for modeling of batch dynamics	716/19	Pasadyn; Alexander J. et	17	r r	 	US 6698009	<u> </u>	
-		US 6427093	USPAT	20020730	hased upon integrated metrol Method and apparatus for	700/121	al. Toprac;				US 6427093		
Ĺ		B1 US 6419801	USPAT	20020716	optimal wafer-by-wafer nrncessing Method and apparatus for	204/192	Anthony J. Smith, Jr.;	ļļ	rr	<u> </u>	LIC 6410001) : 3 	
Γ.		B1 US 8383402	LISPAT	20020507	monitoring plasma processing operations Method and apparatus for	13 216/60	Michael Lane et al. Smith, Jr.;	F7 1		'n		r	
ľ		B1	! !		monitoring plasma		Michael Lane et	₩.	ה ה	. <u>.i</u>	<u>:</u>	r	
ſ	-		USPAT	20010814	Method and apparatus for monitoring plasma ntocessing operations	700/108	Smith, Jr.; Michael Lane et al.	F 1	o c	n	US 6275740	c	
٢	-	US 6269278 B1	USPAT	20010731	Method and apparatus for monitoring plasma	700/121	Smith, Jr.; Michael Lane et	P.		C	US 6269278	Г	
r		US 6261470 B1	USPAT	20010717	nrocessing operations Method and apparatus for monitoring plasma	216/60	Smith, Jr.; Michael Lane et	7		r	US 6261470	r	
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٠		US 6246473	USPAT	20010612	procession operations Method and apparatus for	356/316	lal	 -	· 	.	US 6246473	г	
٠	<u>.</u>	US 6223755	USPAT	20010501	monitoring plasma processing operations Method and apparatus for	134/1.1	al Smith .lr			·- 	US 6223755		
J.	- 1		USPAT	20010424	monitoring plasma processing operations Method and apparatus for	438/7	Michael Lane et al Smith, Jr.;	ŀ÷			US 6221679	r.	
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۱.	1	JS 6090302 A	USPAT	20000718	monitoring plasma procession operations Method and apparatus for	216/60	Michael Lane et al Smith Jr		· ·	·	US 6090302	ir.	
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문 81		optimal wafer-by-wafer	<u> </u>	Anthony J. CCCC
US 6419901 USP E B1	PAT 20020716	Method and apparatus for monitoring plasma	204/192. 13	Smith, Jr.; US 6419801 C Michael Lane et 😿 🗅 🗅 🗅 🗆
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16 US 6269278 USP	AT 20010731	nrncessing onerations Method and apparatus for monitoring plasma	700/121	al. Smith, Jr.; Michael Lane et & C C C C C
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18 US 6254717 USP	AT 20010703	monitoring plasma nmoessing operations Method and apparatus for	158/345.	al
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22 US 6192926 USP, IT B1	AT 20010227	Method and apparatus for monitoring plasma	118/723 AN	Smith, Jr.; Michael Lane et 🗗 🗆 🗆 🗀 🗀
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25 US 6157447 A USP/	AT 20001205	nrncessing onerations Method and apparatus for monitoring plasma	356/316	al Smith, Jr.; Michael Lane et ♥ □ □ □ □ □ □ □
26 US 8134005 A USP/	AT 20001017	nrncessing operations Method and apparatus for monitoring plasma	358/451	al. Smith, Jr.; Michael Lane et ♥ ୮ ୮ ୮ ୮
27 US 6132577 AUSP	AT 20001017	nrocession operations Method and apparatus for	204/298.	al. Smith, Jr.; Michael Lane et デ ロロロロロロロロロロロロロロロロロロロロロロロロロロロロロロロロロ
7 26 US 6123983 A USP/	AT 20000926	monitoring plasma nrncessing operations Method and apparatus for	32 427/10	al Smith .ir US 6123983
7 29 US 6090302 A USP/	AT 20000718	monitoring plasma nrncessing noerations Method and apparatus for	216/60	Michael Lane et 💆 🗀 🗀 🖂 🖂 🖂 🖂 Smith, Jr.: US 6090302
US 6077386 A'USPA	AT 20000620	monitoring plasma		Michael Lane et ♥ □ □ □ □
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US 6041270 A USP/		Automatic recipe adjust and download based on process control window.		Steffan, Paul J. F F F C US 6041270 F
US 5926690 A USP/	AT 19990720	Run-to-run control process for controlling critical dimensions	438/17	Toprac; Anthony John et C C C C C C C C C C
US 6748280 USP/	AT 20040608	Semiconductor run-to-run control system with state and		ZOU; Jianping et R. C. C. C. US 6748280 C.
US 8825513 USP/	AT 20030923	model navameter estimation Run-to-run control over semiconductor processing	700/121	Lymberopoulos C C C C US 6825513 C
35 P. US 6738682 USP/ B1	AT 20040518	tool,based.upon.mimor.image Method and apparatus for scheduling based on state	700/100	Pasadyn; CCCCUS 6738682 C
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	AT 20040511	Disturbance-free, recipe-controlled plasma	156/345. 24	Kagoshima; US 6733618 C
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